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### Abstract Of The Invention

5 In order to manufacture an integrated optical circuit, a first mask is formed on a first region of a substrate and defines the shape of at least one optical device (such as a waveguide). A second mask is formed on a second region of the substrate and corresponds to an optical structure (such as a periodic array structure or photonic crystal) to be formed in a second region of the substrate distinct from the first region.

10 The first mask and the second mask are each made of a material which substantially resists a predetermined etching gas. The second mask may be formed, patterned, and etched without adversely affecting the characteristics of the first mask.

[illegible]